Atty. Docket No.: 006915 USA P02/FEP/P3I/PJT
RW Ref. No.: APM/001-02-CP1-2

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	
Kenneth Collins, et al.	
Entitled: PLASMA IMMERSION ION IMPLANTATION APPARATUS USING A PLASMA SOURCE HAVING LOW DISSOCIATION AND LOW MINIMUM PLASMA VOLTAGE	Group Art Unit: 2893
	Examiner: Jack S. Chen
Serial No.: 10/646,533	
Filing Date: August 22, 2003	

RESPONSE TO OFFICE ACTION (DOUBLE PATENTING REJECTION) DATED 08/06/2009

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action (Double Patenting) dated August 6, 2009, applicants submit herewith a Terminal Disclaimer to overcome the double patenting rejection.

Although the claims have not been amended, a complete listing of claims is provided and begins on page 2.

Remarks begin on page 17 of this paper.